

 <p><b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  <i>(use as many sheets as necessary)</i></p>		<i>Complete if Known</i>	
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		Art Unit	1756
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## **U.S. PATENT DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Document Number		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
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		US			
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## FOREIGN PATENT DOCUMENTS

## NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), date of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city, and/or country where published.	Translation <sup>6</sup>
MD		YOSHINOBU TSUJI ET AL. : "Fabrication of patterned high-density polymer graft surfaces. II. Amplification of EB-patterned initiator monolayer by surface-initiated atom transfer radical polymerization", POLYMER, ELSEVIER SCIENCE PUBLISHERS B.V, GB, vol. 43, no. 13, June 2002, pages 3837-3841, XP004349557	
MD		RAHUL R. SHAH, ET AL., "Using atom transfer radical polymerization to amplify monolayers of initiators patterned by microcontact printing into polymer brushes for pattern transfer", MACROMOLECULES, vol. 33, no. 2, August 1, 2000, pages 597-605, XP002273494	
MD		KRZYSZTOF MATYJASZEWSKI, et al., "Atom transfer radical polymerization", CHEMICAL REVIEWS, AMERICAN CHEMICAL SOCIETY, EASTON, US, vol. 101, no. 9, December 9, 2001, pages 2921-2990, XP002212148	
MD		YOUNAN XIA, ET AL. "Soft Lithography", ANGEWANDTE CHEMIE. INTERNATIONAL EDITION, VERLAG CHEMIE. WEINHEIM, DE, vol. 37, 1998, pages 550-575, XP002149045	

**\*EXAMINER:** Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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